



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Cheng-Ku CHEN, et al.

Serial No.: 10/798,178

Filed: March 11, 2004

For: METHOD OF FORMING  
POLYSILICON GATE STRUCTURES  
WITH SPECIFIC EDGE PROFILES FOR  
OPTIMIZATION OF LDD OFFSET  
SPACING

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Confirmation No. 5314

Group Art Unit: 2812

Examiner: Cheung Lee

Commissioner for Patents  
Mail Stop Amendment  
P.O. Box 1450  
Alexandria, VA 22313-1450

**AMENDMENT**

Sir:

In response to the Office Action dated October 18, 2005, please amend the above-identified application as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 10 of this paper.